L Number	Hits	Search Text	DB	Time stamp
43	8154	(438/38,622,624,637,778,786,787,958,981,for.489,for.493).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 18:44
50	19	imag$3 near array and ((438/38,622,624,637,778,786,787,958,981,for.489,for.493).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 10:45
-	1	("6384461").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 11:42
-	0	6384461.URPN.	USPAT	2003/02/20 11:40
-	2	("5574292" | "5616524").PN.	USPAT	2003/02/20 11:40
-	1219	first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 17:05
-	366	(first near2 (dielectric passivation insulating insulation passivating) with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second near2 (dielectric passivation insulating insulation passivating) with ((oxide dioxide di near oxide))) and (first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:05
-	308	((first near2 (dielectric passivation insulating insulation passivating) with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second near2 (dielectric passivation insulating insulation passivating) with ((oxide dioxide di near oxide))) and (first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide)))) and (438/$6 257/$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 17:06

-	133	(((first near2 (dielectric passivation insulating insulation passivating) with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second near2 (dielectric passivation insulating insulation passivating) with ((oxide dioxide di near oxide))) and (first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide)))) and (438/$6 257/$6)) and ("a" amorphous) near (silicon si)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB,	2003/02/20 14:21
-	93	mushroom near (shape shaped) near2 electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 14:24
-	2	(first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide))) and (mushroom near (shape shaped) near2 electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 14:25
-	2	((first near2 (dielectric passivation insulating insulation passivating) with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second near2 (dielectric passivation insulating insulation passivating) with ((oxide dioxide di near oxide))) and (first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide)))) and 257/458	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 14:27

–	70	(((first near2 (dielectric passivation insulating insulation passivating) with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second near2 (dielectric passivation insulating insulation passivating) with ((oxide dioxide di near oxide))) and (first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide)))) and (438/$6 257/$6)) and (source drain "s/d") near2 electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 14:29
–	2	(first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide))) and lateral with leak$3 with current	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 14:47
–	3	(first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide))) and lateral$2 with leak$3 with current	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 14:49
–	161	(first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide))) and leak$3 with current	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 14:49
–	308	((first near2 (dielectric passivation insulating insulation passivating) with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second near2 (dielectric passivation insulating insulation passivating) with ((oxide dioxide di near oxide))) and (first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide)))) and (438/$6 257/$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 17:09

–	521	first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide)) and (438/$6 257/$6) not (((first near2 (dielectric passivation insulating insulation passivating) with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second near2 (dielectric passivation insulating insulation passivating) with ((oxide dioxide di near oxide))) and (first with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide)) and second with ((oxide dioxide di near oxide))))) and (438/$6 257/$6))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/20 17:14
–	72	(dual two) near2 (dielectric passivation insulating insulation passivating) with ((silicon near (oxynitride oxy near nitride) "siO.sub.xN.sub.y" "si O.sub.x N.sub.y" "si O.sub.y N.sub.x" "siO.sub.yN.sub.x") (benzocyclobutene benzo near cyclo near butene benzo near cyclobutene benzocyclo near butene BCB) (polyamide poly near amide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:11
–	6	("4700457" | "4985718" | "4990463" | "5006481" | "5262354" | "5312512").PN.	USPAT	2003/02/21 09:22
–	3	("5232970" | "5288989" | "5416233").PN.	USPAT	2003/02/21 09:23
–	9	("4577395" | "4833094" | "5026659" | "5162248" | "5270241" | "5275974" | "5292679" | "5384152" | "5604696").PN.	USPAT	2003/02/21 09:23
–	2	full near fill near factor near image near array	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:46
–	2	full near fill near factor near image near array	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:48
–	10	fill near factor near imag$3 near array	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:49
–	8	fill near factor near image near array	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:48
–	10	fill near2 factor near imag$3 near array	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:51

-	12161	imag$3 near array	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 10:45
-	1	(imag$3 near array) and upper near electrode with (ito (tin indium) near2 oxide) with pattern$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:54
-	50	(imag$3 near array) and electrode with (ito (tin indium) near2 oxide) with pattern$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:54
-	49	((imag$3 near array) and electrode with (ito (tin indium) near2 oxide) with pattern$3) not ((imag$3 near array) and upper near electrode with (ito (tin indium) near2 oxide) with pattern$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/21 09:55